FORM PTO-1449 (MODIFIED) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary) (37 CFR 1.98(b))

ATTY. DOCKET NO. 02-40171-US	10/633,372
APPLICANT Anguel Nikolov et al.	
FILING DATE August 1, 2003	GROUP 2872

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		PATENT NUMBER	ISSUE DATE	PATENTEE	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
CEC		4,615,034	09/86	Von Gunten et al			
		4,638,669	01/87	Chou			
		4,650,289	03/87	Kuwahara			
		4,732,444	03/88	Papuchon et al			
		4,763,972	08/88	Papuchon et al			
		4,778,234	10/88	Papuchon et al			
		4,998,793	03/91	Henry et al			
		5,077,816	12/91	Glomb et al			
		5,088,105	02/92	Scifres et al			
		5,091,981	02/92	Cunningham			
		5,283,845	02/94	Ip			
		5,299,212	03/94	Koch et al			
		5,461,246	10/95	Chou			
		5,467,415	11/95	Presby			
		5,617,234	04/97	Koga et al			
		5,654,818	08/97	Yao			
		5,691,989	11/97	Rakuljic et al			
		5,706,301	01/98	Lagerstrom			
		5,719,976	02/98	Henry et al			
		5,726,805	03/98	Kaushik et al			
		5,772,905	06/98	Chou			
		5,777,793	07/98	Little et al			
		5,793,784	08/98	Wagshul et al			
CEC		5,820,769	10/98	Chou			

EXAMINER Craig A. Curtis DATE CONSIDERED 23 Sept. '04

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CHC		5,848,080	12/98	Dahm			
		5,852,688	12/98	Brinkman et al			
		5,870,421	02/99	Dahm			
		5,956,216	09/99	Chou			
		5,966,483	10/99	Chowdhury			
		5,973,316	10/99	Ebbesen et al			
		5,973,784	10/99	Szwaykowski et al			
		6,035,089	03/00	Grann et al			
		6,037,644	03/00	Daghighian et al			
		6,040,936	03/00	Kim et al			
		6,052,238	04/00	Ebbesen et al			
		6,064,506	05/00	Koors			
		6,069,380	05/00	Chou et al			
		6,075,915	06/00	Koops et al			
		6,101,300	08/00	Fan et al			
		6,122,103	09/00	Perkins et al			
		6,122,301	09/00	Tei et al			
		6,125,220	09/00	Copner et al			
		6,130,969	10/00	Villeneuve et al			
		6,137,939	10/00	Lesesky et al			
		6,154,318	11/00	Austin et al			
		6,154,479	11/00	Yoshikawa et al			
		6,169,825	01/01	Morey et al			
CHC		6,175,667	01/01	Wang et al			

EXAMINER90	Craig H. Curtis	DATE CONSIDERED	23 Sept. 04

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CLC		6,191,890	02/01	Baets et al			
		6,198,557	03/01	Dultz et al			
		6,198,860	03/01	Johnson et al			
		6,208,463	03/01	Hansen et al			
		6,215,928	04/01	Friesem et al			
		6,233,375	05/01	Lang et al			
		6,233,380	05/01	Ferrieu			
		6,235,141	05/01	Feldman et al			
		6,240,109	05/01	Shieh			
		6,251,297	06/01	Komuro et al			
		6,252,709	06/01	Sato			
		6,253,009	06/01	Lestra et al			
		6,260,388	07/01	Borrelli et al			
		6,262,002	07/01	Carey			
		6,263,002	07/01	Hsu et al			
		6,275,291	08/01	Abraham et al			
		6,285,810	09/01	Fincato et al			
		6,288,840	09/01	Perkins et al			
		6,309,580	10/01	Chou			
		6,317,554	11/01	Kosaka et al			
		6,324,192	11/01	Tayebati			
		6,339,603	01/02	Flanders et al			
		6,349,103	02/02	Chung et al			
CLC		6,353,623	03/02	Munks et al			

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CHC		6,359,915	03/02	Koch et al			
		6,370,177	04/02	Genei et al			
		6,371,662	04/02	Leard et al			
		6,374,016	04/02	Albert el al			
		6,400,860	06/02	Chandrasekhar et al			
		6,410,416	06/02	Dodabalapur et al			
		6,482,742	11/02	Chou			
		6,518,189	02/03	Chou			
		6,618,104	09/03	Date et al			
		6,661,952	12/03	Simpson et al			
		6,692,797	02/04	Owen et al			
		6,713,238	03/04	Chou et al			
CHC		Re.35,337	09/96	Patel et al			

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EXAMINER	Craig H. Curtis	DATE CONSIDERED	23 Sept. '04

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EXAMINER	Bruce R. Curtis	DATE CONSIDERED	23 Sept. 04

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CAE			

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